

Jc872 U.S. PTO
06/09/2004



Form PTO-1449

LIST OF PATENTS AND
PUBLICATIONS
FOR INFORMATION
DISCLOSURE STATEMENT
(Use Several Sheets if Necessary)

APPLICANT: Pawitter Mangat et al.

ATTY. DOCKET #: SC11661TP

APPL. #: Unknown

FILING DATE: Concurrently Herewith

GROUP: Unknown

#2

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
SPR	AA	US 6,261,726 B1	Jul.17,'01	Brooks et al.	430	5	Dec.6,'99
SPR	AB	US 6,221,537 B1	Apr.24,'01	Thompson et al.	430	5	Dec.19,'97
SPR	AC	6,159,558	Dec.12,'00	Wolfe et al.	427	523	Oct.12,'99
SPR	AD	6,140,020	Oct.31,'00	Cummings	430	296	Nov.30,'98
SPR	AE	6,124,063	Sep.26,'00	Dauksher et al.	430	5	Jul.30,'98
SPR	AF	6,063,246	May 16,'00	Wolfe et al.	204	192.16	May 23,'97
SPR	AG	6,051,346	Apr.18,'00	Kornblit et al.	430	5	Jul.23,'98
SPR	AH	5,972,794	Oct.26,'99	Katakura	438	704	Mar.18,'98
SPR	AI	5,942,760	Aug.24,'99	Thompson et al.	250	492.2	Nov.3,'97
SPR	AJ	5,912,095	Jun.15,'99	Katakura	430	5	Jun.3'97
SPR	AK	5,899,728	May 4,'99	Mangat et al.	438	459	Dec.22,'97

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	PUBLICATION DATE (#43)	COUNTRY	CLASS	SUBCLASS
	AL					
	AM					
	AN					
	AO					
	AP					

OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, Etc.)

SPR	AR	Donald W. Pettibone et al., "UV Inspection of EUV and SCALPEL Reticles", 20 th Annual BACUS Symp. on Photomask Tech.; Proceedings of SPIE, Vol.4186 (2001);0277-786X/01, pgs.241-249.
SPR	AS	Brian J. Grenon et al., "20 th Annual BACUS Symposium on Photomask Technology", 20 th Annual BACUS Symp. on Photomask Tech.; Proceedings of SPIE, Vol.4186 (2001);0277-786X, pgs. 717-723.
SPR	AT	H.C.Pfeiffer et al., "Projection reduction exposure with variable axis immersion lenses: Next generation lithography", J. Vac. Sci. Technol. B 17(6), Nov/Dec 1999 American Vacuum Society, pgs. 1-7.
SPR	AU	S. Kawata et al., "Stencil reticle development for electron beam projection system", J. Vac. Sci. Technol. B 17(6), Nov/Dec 1999 American Vacuum Society, pgs. 2864-2867.
SPR	AV	I.W. Rangelow et al., "p-n junction-based wafer flow process for stencil mask fabrication", J. Vac. Sci. Technol. B 16(6), Nov/Dec 1998 American Vacuum Society, pgs. 3592-3598.
SPR	AW	P. Hudek et al., "Directly sputtered stress-compensated carbon protective layer for silicon stencil masks", J. Vac. Sci. Technol. B 17(6), Nov/Dec 1999 American Vacuum Society, pgs. 3127-3131.

EXAMINER

Mohamedulla

DATE CONSIDERED

10/20/03

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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EXAMINER INITIAL		DOCUMENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
SDM	BA	5,674,413	Oct.7,'97	Pfeiffer et al.	219	121.25	Nov.22,'95
SPM	BB	5,464,711	Nov.7,'95	Mogab et al.	430	5	Aug.1,'94
	BC						
	BD						
	BE						
	BF						
	BG						
	BH						
	BI						
	BJ						
	BK						

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	PUBLICATION DATE (#43)	COUNTRY	CLASS	SUBCLASS
	BL					
	BM					
	BN					
	BO					
	BP					

OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, Etc.)

	BR	
	BS	
	BT	
	BU	
	BV	
	BW	
	BX	
	BY	
	BZ	

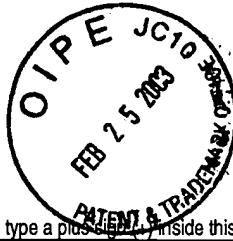
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Substitute for form 1449A/PTO		<i>RECEIVED FEB 28 2003 GPO/HD 1700</i>	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>		<i>Complete if Known</i>	
Sheet	of	Application Number	09/927,024
		Filing Date	August 9, 2001
		First Named Inventor	Pawitter Mangat
		Group Art Unit	1756
		Examiner Name	Unassigned
		Attorney Docket Number	SC11661TP

U. S. PATENT DOCUMENTS

Examiner Initials*	Cite No. 1	U.S. Patent Document ¹		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code ² (if known)			
SRM	CA	2002/0001964	A1	Choi	01/30/2002	
SRM	CB	6,316,151	B1	Kim <i>et al.</i>	11/13/2001	
SRL	CC	6,004,700		Greschner <i>et al.</i>	12/21/1999	
SM	CD	5,935,739		Bayer <i>et al.</i>	08/10/1999	
SRA	CE	5,523,185		Goto	06/04/1996	
SSR	CF	5,500,312		Harriott <i>et al.</i>	03/19/1996	

FOREIGN PATENT DOCUMENTS

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. 1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
<i>SPM</i>	CH	PCT/US02/24164 Search Report mailed February 5, 2003.	

Examiner: Signature:	mohamed ulla	Date Considered	10/20/03
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¹ Unique citation designation number. ² See Kinds of U.S. Patent Documents. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark here if English Language Translation is attached.



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<p style="text-align: center;">INFORMATION DISCLOSURE STATEMENT BY APPLICANT</p> <p>(use as many sheets as necessary)</p>				Complete if Known	
				Application Number	09/927,024
				Filing Date	08-09-2001
				First Named Inventor	Pawitter Mangat
				Group Art Unit	1756
				Examiner Name	Saleha R. Mohamedulla
Sheet	1	of	1	Attorney Docket Number	SC11661TP

U. S. PATENT DOCUMENTS

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Examiner Signature	Mohamed J. Isha	Date Considered	10/20/03
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